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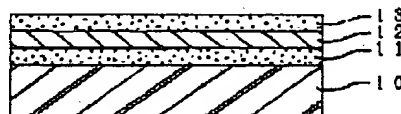
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**FUKUYOSHI KENZO
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TAKANASHI SHOJI**(54) **SPUTTERING TARGET**

(57) Abstract:

PROBLEM TO BE SOLVED: To provide a sputtering target capable of effectively forming transparent thin films excellent in moisture resistance at the time of forming transparent thin films as conductive films having a constitution sandwiching a silver base thin film and by which the silver base thin film is hard to be applied with damage at the time of the film forming.

SOLUTION: This sputtering target is composed of a sintered body of mixed oxides obtd. by incorporating mixed oxides using indium oxide and cerium oxide as base materials with tin oxide by an amt. smaller than the mixing ratios of each base material and applied at the time of forming transparent thin films 11 and 13 as conductive films having a constitution sandwiching a silver base thin film 12.



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